

ABSTRACT OF THE DISCLOSURE

RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN

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A resist composition containing a resin component (A1) that has a constitutional unit (a1) containing an acid-decomposable group and a constitutional unit (a10) represented by General Formula (a10-1), and a plasticizer component (Z) that has a constitutional unit (z1) represented by General Formula (z1-1) and does not contain an acid-dissociable group. In the resist composition, a content of the plasticizer component (Z) is 50 parts by mass or less with respect to 100 parts by mass of the resin component (A1), and a solid content concentration is 25% by mass or more (in the formula, Wa^{x1} represents an aromatic hydrocarbon group, Vz^0 represents a single bond or a divalent hydrocarbon group which does not contain an acid-dissociable group, and Rz^0 represents a hydrocarbon group which does not contain a hydrogen atom or an acid-dissociable group).

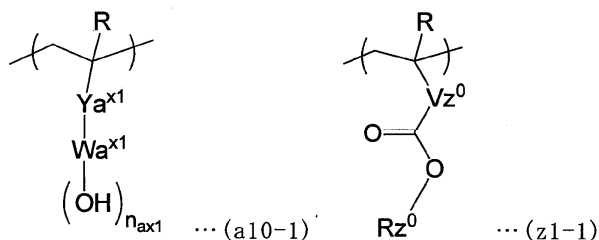


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